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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/588,708	08/09/2006	Toshiaki Sasaki	81844.0052	2456	
2602L 7550 09/24/2009 HOGAN & HARTSON L.L.P.			EXAM	EXAMINER	
1999 AVENUE	E OF THE STARS	GARDNER, SHANNON M			
SUITE 1400 LOS ANGELE	S, CA 90067	ART UNIT	PAPER NUMBER		
			1795		
			NOTIFICATION DATE 09/24/2009	DELIVERY MODE ELECTRONIC	

## Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail address(es):

ctkeyner@hhlaw.com LAUSPTO@hhlaw.com lbrivero@hhlaw.com

## Advisory Action Before the Filing of an Appeal Brief

Ī	Application No.	Applicant(s)	
	10/588,708	SASAKI ET AL.	
	Examiner	Art Unit	
	Shannon Gardner	1795	

	Shannon Gardner	1795				
The MAILING DATE of this communication appe	ars on the cover sheet with the	orrespondence add	ress			
THE REPLY FILED 20 August 2009 FAILS TO PLACE THIS AF	PPLICATION IN CONDITION FOR	ALLOWANCE.				
<ol> <li>Sign reply was filed after a final rejection, but prior to or on application, applicant must timely file one of the following application in condition for allowance, (2) a Notice of Appe for Continued Examination (RCE) in compliance with 37 C pendos;</li> </ol>	the same day as filing a Notice of replies: (1) an amendment, affidavi eal (with appeal fee) in compliance FR 1.114. The reply must be filed	Appeal. To avoid abar t, or other evidence, w with 37 CFR 41.31; or	hich places the (3) a Request			
b) The period for reply expires on: (1) the mailing date of this A	<ul> <li>a) The period for reply expiresmonths from the mailing date of the final rejection.</li> <li>b) The period for reply expires on: (1) the mailing date of this Advisory Action, or (2) the date set forth in the final rejection, whichever is later.</li> </ul>					
no event, however, will the statutory period for reply expire to Examiner Note: If box 1 is checked, check either box (a) or ( MONTHS OF THE FINAL REJECTION. See MPEP 706,07(	b). ONLY CHECK BOX (b) WHEN THE					
Extensions of time may be obtained under 37 CFR 1.136(a). The date have been filed is the date for purposes of determining the period of ext under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the s	on which the petition under 37 CFR 1.1 ension and the corresponding amount	of the fee. The appropria	ate extension fee			
under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the set forth in (b) above, if checked. Any reply received by the Office later may reduce any earned patent term adjustment. See 37 CFR 1.704(b). NOTICE OF APPEAL	than three months after the mailing dat	e of the final rejection, e	e action; or (2) as /en if timely filed,			
The Notice of Appeal was filed on A brief in comp.	liance with 37 CER 41 37 must be	iled within two months	of the date of			
filing the Notice of Appeal (37 CFR 41.37(a)), or any exter Notice of Appeal has been filed, any reply must be filed wi	sion thereof (37 CFR 41.37(e)), to	avoid dismissal of the				
<u>AMENDMENTS</u>						
<ol> <li>The proposed amendment(s) filed after a final rejection, t</li> <li>They raise new issues that would require further cor</li> <li>They raise the issue of new matter (see NOTE belowed)</li> </ol>	sideration and/or search (see NO		cause			
(c) They are not deemed to place the application in bet appeal; and/or		lucing or simplifying t	ne issues for			
(d) ☐ They present additional claims without canceling a c	corresponding number of finally reje	ected claims.				
NOTE: (See 37 CFR 1.116 and 41.33(a)).  4. The amendments are not in compliance with 37 CFR 1.12	21 See attached Notice of Non Co	mpliant Amandment (	DTOL 224)			
<ol> <li>Applicant's reply has overcome the following rejection(s):</li> </ol>		ripliant Amendment (	- TOL-324).			
<ul> <li>Applicant's reply has overcome the following rejection(s):</li> <li>Newly proposed or amended claim(s) would be allowable if submitted in a separate, timely filed amendment canceling the non-allowable claim(s).</li> </ul>						
7. For purposes of appeal, the proposed amendment(s): a) [ how the new or amended claims would be rejected is prov		be entered and an e	planation of			
The status of the claim(s) is (or will be) as follows: Claim(s) allowed:						
Claim(s) objected to: Claim(s) rejected: <u>1-3, 5-7, 9-11</u> .						
Claim(s) withdrawn from consideration:  AFFIDAVIT OR OTHER EVIDENCE						
8. The affidavit or other evidence filed after a final action, but because applicant failed to provide a showing of good and was not earlier presented. See 37 CFR 1.116(e).						
The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to o showing a good and sufficient reasons why it is necessary	vercome <u>all</u> rejections under appea	l and/or appellant fail:	s to provide a			
10. The affidavit or other evidence is entered. An explanation						
REQUEST FOR RECONSIDERATION/OTHER  11. ☑ The request for reconsideration has been considered but see Continuation Sheet.	does NOT place the application in	condition for allowan	ce because:			
12. Note the attached Information Disclosure Statement(s). (	PTO/SB/08) Paper No(s)					
/Jennifer K. Michener/ Supervisory Patent Examiner, Art Unit 1795	/S. G./ Examiner, Art Unit 1795					
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Continuation of 11. does NOT place the application in condition for allowance because:

Applicant has amended claim 1 to include the limitations from the previously listed claim 8, which is now cancelled.

The Examiner notes that claim 1 is still unpatentable over Tawada in view of Matsui and Robinson. Tawada in view of more than 95 nm. However, it is known in the art to create a substrate containing silica micro-particles (such soles used in modified Tawada) with particles having an average diameter of 5 to 25 nm, thus creating an improved flexible substrate surface with good high-temperature dimensional stability and high optical clarify, as staught by Robinson (paragraphs (0012)-[10018] co025]). Therefore, it vould have been obvious to one of ordinary skill in the art at the time of the invention of neutron particles having an average diameter of 5 to 25 m in the invention of modified Tawada to create an improved substrate surface as taucht by Robinson.

The Examiner further notes that in the case where the claimed ranges 'overlap or lie inside ranges disclosed by the prior art a prima facie case of obviousness exists. Further still, the teachings of Tawada provide for micro-particles of 0.1 to 1.0 microns (100nm to 1000nm). A prima facie case of obviousness exists where the claimed ranges and prior art ranges do not overlap but are close enough that one skilled in the art would have expected them to have the same properties (see MPEP 2144.05).

Claims 2-3, 5-7 and 9-11 stand rejected as previously presented in the Office Action dated 6/22/2009.

Applicant argues that "the Office has failed to present an adequate showing as to why Tawada's teaching of an average diameter of 0.1 to 1.0 microns should be ignored in favor of Robinson's teaching of an average diameter of 5 to 25 nm" (pp 7 of Arguments).

The Examiner directs Applicant to the final Office Action of 6/22/2009 for a full discussion of the references. Tawada teaches a general range for the average diameter of his mirro-particles. However, one of ordinary skill in the art at the time of the invention would have looked to the teachings of the prior art for ways to further develop the substrate containing the micro-particles. Particularly, one of ordinary skill would have looked to the teachings of Robinson for information on improvements to the substrate by utilizing micro-particles sized 5 mm to 25 mm.

Applicant argues that "The surfaces disclosed in Matsui are different than the surfaces of the present invention...Matsui teaches the uneveness of the ZnO layer but is silent as to the uneveness of the transparent foundation layer" (pp 8 of Arguments).

The Examiner notes that Matsu is relied upon as a general teaching regarding the use of textured substrates with a RMS roughness of a specified value to improve the conversion efficiency (see abstract and Introduction). It would have been obvious to one of ordinary skill in the art at the time of the invention to apply this teaching to the transparent insulating substrate of Tawada to improve the conversion efficiency.